## What Is Claimed Is:

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- 1. An exposure system, comprising:
- a compensation unit to receive at least one adjustment value of a corresponding equipment parameter, and compensate a corresponding overlay parameter according to the adjustment value and an adjustment formula corresponding to the equipment parameter; and
- an exposure device to perform overlay and exposure
  processes on a wafer using the compensated overlay
  parameter.
  - 2. The exposure system as claimed in claim 1 wherein the compensation unit calculates a compensation value according to the adjustment value and the adjustment formula, and compensates the overlay parameter using the compensation value.
  - 3. The exposure system as claimed in claim 2 wherein the equipment parameter is FIA\_X, the affected overlay parameter is Offset\_X, and the adjustment formula is,
  - B = (-1.0883\*A) 0.0016,
  - wherein A is the adjustment value and B is the compensation value.
  - The exposure system as claimed in claim 2 wherein the equipment parameter is FIA\_Y, the affected overlay parameter is Offset Y, and the adjustment formula is,
  - B = (-1.0232\*A) 0.0023,
  - wherein A is the adjustment value and B is the compensation value.

- 5. The exposure system as claimed in claim 2 wherein the equipment parameter is LSA\_X, the affected overlay parameter is Offset\_X, and the adjustment formula is

  B = (-0.9958\*A)+0.0011,

  wherein A is the adjustment value and B is the compensation
- The exposure system as claimed in claim 2 wherein the equipment parameter is LSA\_Y, the affected overlay parameter is Offset Y, and the adjustment formula is,
- B = (-1.0042\*A) 0.0004,

value.

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- wherein A is the adjustment value and B is the compensation value.
  - 7. The exposure system as claimed in claim 2 wherein the equipment parameter is Matching Offset X, the affected overlay parameter is Shot Scaling X, and the adjustment formula is,
- A B = (-84.853\*A) + 0.0639,
- wherein A is the adjustment value and B is the compensation value.
- 1 8. The exposure system as claimed in claim 2 wherein the 2 equipment parameter is Machine Scaling Y, the affected overlay 3 parameter is Shot Scaling Y, and the adjustment formula is,
- B = (-1.0053\*A) 0.0193,
- wherein A is the adjustment value and B is the compensation value.
- 9. The exposure system as claimed in claim 2 wherein the equipment parameter is Shot Skew, the affected overlay parameter is Shot Ortho, and the adjustment formula is,

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4 B = (-0.9422\*A) + 0.0094,5 wherein A is the adjustment value and B is the compensation 6 value. The exposure system as claimed in claim 2 wherein the 1 2 equipment parameter is Machine Shot Rot, the affected overlay 3 parameter is Shot Rot, and the adjustment formula is, 4 B = (-1.0247\*A) - 0.0214,wherein A is the adjustment value and B is the compensation 5 value. 6 1 11. An exposure method, comprising the steps of: receiving at least one adjustment value of a corresponding 2 equipment parameter; 3 compensating a corresponding overlay parameter according 4 5 to the adjustment value and an adjustment formula corresponding to the equipment parameter; and 6 7 performing overlay and exposure processes on a wafer using 8 the compensated overlay parameter. 1 The exposure method as claimed in claim 11 further 2 comprising calculating a compensation value according to the 3 adjustment value and the adjustment formula, and compensating 4 the overlay parameter using the compensation value. 1 13. The exposure method as claimed in claim 12 wherein the

B = (-1.0883\*A) - 0.0016,

Offset X, and the adjustment formula is,

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wherein A is the adjustment value and B is the compensation value.

equipment parameter is FIA X, the affected overlay parameter is

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value.

- The exposure method as claimed in claim 12 wherein the 1. equipment parameter is FIA Y, the affected overlay parameter is 3 . Offset Y, and the adjustment formula is, B = (-1.0232\*A) - 0.0023,4 . wherein A is the adjustment value and B is the compensation 5 value. 1 The exposure method as claimed in claim 12 wherein the equipment parameter is LSA X, the affected overlay parameter is 2 Offset X, and the adjustment formula is, 4 B = (-0.9958\*A) + 0.0011,wherein A is the adjustment value and B is the compensation 5 value. 6 The exposure method as claimed in claim 12 wherein the 1 2 equipment parameter is LSA Y, the affected overlay parameter is 3 Offset Y, and the adjustment formula is, B = (-1.0042\*A) - 0.0004,4 5 wherein A is the adjustment value and B is the compensation 6 value. The exposure method as claimed in claim 12 wherein the 1 equipment parameter is Matching Offset X, the affected overlay 2. 3 parameter is Shot Scaling X, and the adjustment formula is, B = (-84.853\*A) + 0.0639,4 wherein A is the adjustment value and B is the compensation 5
  - 18. The exposure method as claimed in claim 12 wherein the equipment parameter is Machine Scaling Y, the affected overlay parameter is Shot Scaling Y, and the adjustment formula is,

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A = (-1.0053\*A) - 0.0193,

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- wherein A is the adjustment value and B is the compensation value.
- 1 19. The exposure method as claimed in claim 12 wherein the 2 equipment parameter is Shot Skew, the affected overlay parameter 3 is Shot Ortho, and the adjustment formula is,
  - B = (-0.9422\*A) + 0.0094,
- wherein A is the adjustment value and B is the compensation value.
- The exposure method as claimed in claim 12 wherein the equipment parameter is Machine Shot Rot, the affected overlay parameter is Shot Rot, and the adjustment formula is,
- B = (-1.0247\*A) 0.0214,
- wherein A is the adjustment value and B is the compensation value.